

Study of Insulator-Metal transition of VO₂ thin films with ultrafast optical pulses

Abstract

VO₂ has been a popular material to study in the past few decades as it has a Variable ND filter reversible insulator-metal transition (IMT) when heated past 340K or stimulated Legend Elite 800nm with an ultrafast optical pulse. The resistance and optical properties change by FWHM 100fs several orders of magnitude, making it an attractive candidate for low loss Repetition rate 1kHz plasmonic devices, ultrafast switches, or smart windows. We study the dynamics of the transition of VO₂ thin films on different substrates with femtosecond pulses in a pump-probe experiment in order to better understand the mechanisms behind the transition. We have measured the IMT at several Variable Delay different temperatures to investigate any change in the dynamics of the transition. We also study the Raman spectroscopy of VO₂ thin films heated through the transition. The effects of the different substrates on the transition of the VO₂ thin film will be discussed. VO_2 sample mounted in a Insulator-Metal Transition t>0 cryostat The probe beam hits sample before pump beam Low temperature Probe-[–]Pump monoclinic phase t=0 The pump beam hits $T > T_{\rm c}$ sample $T < T_{\rm c}$ simultaneously with probe beam E-E_f(eV) 1.00 MM V 3d / (a.u.) 86'0 C_R a_M↑ C, **b**_R **Ο 2p** σ $\sim\sim$ $\sim\sim$ 0.96 Electronic band structure change narrows band gap. 0.8 0.0 -0.8Time (ps) _∎_ 30mJ/cm^2 VO₂ in cryostat: -∎- 50mJ/cm^2 Room Temperature -■-75mJ/cm^2 _**■**— 100mJ/cm^2 1.00 — 120mJ/cm^2 Samples 0.98 Thin films of VO_2 grown by sputtering Three different substrates: quartz (SiO₂), sapphire (Al₂O₃), Rutile (TiO₂) 0.96 TiO (011) VO_2 on Rutile 0.94 -0.5 0.0 Grain size ~10nm Time (ps) Substrate Effects Rutile(110nm Sapphire (101nm) Long Term Behavior 35 35.5 36 36.5 37 37.5 38 38.5 2θ **(deg)** VO2 on TiO2 60mJ/cm² (0 degrees)
VO2 on TiO2 60mJ/cm² (90 degrees) /O2 on SiO2 60mJ/cm^2 VO_2 on Quartz: VO_2 on Sapphire Grain Size ~70nm Grain Size ~20nm 🔒 40 50



¹ a. Pashkin, C. Kübler, H. Ehrke, R. Lopez, a. Halabica, R.F. Haglund, R. Huber, and a. Leitenstorfer, Physical Review B 83, 195120 (2011)



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Ultrafast Measurement



Time (ps)



We have compared the different behavior of films grown at different substrates. By looking at the response from the time dependent measurement, the change in amplitude of the Raman spectrum, and the change in intensity of reflectivity associated with IMT, we find a strong dependence on differences in microstructure. In future studies, we will study further how the ultrafast response and recovery differs for films with different strain and microstructure.

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